



## ABSTRACT

The invention reduces the effects of stitching errors from re-scaling or re-positioning in the fabrication of fiber Bragg gratings or the mask used in such fabrication. A first embodiment of the invention preferably uses characteristics of stitching errors to compensate for the stitching errors themselves. By increasing the number of stitching errors, errors caused by the stitching errors can be reduced. A second embodiment uses continuous writing of the desired pattern, wherein the desired pattern is snapped to a grid that can be written by the fabrication equipment. Using continuous writing eliminates stitching errors in the resulting gratings.

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